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Substitute for form 1449A/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(use as many sheets as necessary)</i>				<i>Complete if Known</i>	
				Application Number	TO BE ASSIGNED (DIV2)
				Filing Date	March 8, 2002
				First Named Inventor	Bruce W. Smith
				Group Art Unit	2851
				Examiner Name	Hung NGUYEN
				Attorney Docket Number	81468.284421
Sheet	1	of	2		

[illegible][illegible]

Examiner Signature	H. Nguyen	Date Considered	6/18/2003
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¹ Unique citation designation number. ² See attached Kinds of U.S. Patent Documents. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶ Applicant is to place a check mark here if English language Translation is attached.

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Substitute for form 1449B/PTO			Complete if Known	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)			Application Number	TO BE ASSIGNED (DIV2)
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			First Named Inventor	Bruce W. Smith
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			Examiner Name	Hung NGUYEN
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Sheet	2	of	2	

OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
HN	15	S. Asai, et al., "High Performance Optical Lithography Using a Separated Light Source", <u>J. Vac. Sci. Technology</u> , Vol B 10(6), pp. 3023-3026, (November/December 1992).	
	16	E. Tamechika, et al., "Investigation of Single Sideband Optical Lithography Using Oblique Incidence Illumination", <u>J. Vac. Sci. Technology</u> , Vol. B 10(6), pp. 3027-3031, (November/December 1992).	
	17	W.N. Partlow, et al., "Depth of Focus and Resolution Enhancement for i-line and Deep-UV Lithography Using Annular Illumination", <u>SPIE Optical/Laser Microlithography</u> , Vol. 1927, pp. 137-156, (1993).	
	18	T. Ogawa, et al., "The Effective Light Source Optimization With the Modified Beam For the Depth-of-Focus Enhancements", <u>SPIE Optical Laser Microlithography</u> , Vol. 2197, pp. 19-30, (1994).	
	19	T. Ogawa, et al., "Sub-Quarter Micron Optical Lithography With Practical Super Resolution Technique", <u>SPIE Optical Laser Microlithography VIII</u> , Vol. 2440, pp. 772-783, (1995).	
	20	B. W. Smith, et al., "Illumination Pupil Filtering Using Modified Quadrupole Apertures", <u>SPIE Optical Microlithography XI</u> , Vol. 3334, pp. 37-47, (1998).	
	21	B.W. Smith, et al., "Influences of Off-Axis Illumination on Optical Lens Aberration", <u>J. Vac. Sci. Technology</u> , Vol. B16(6) 3398, pp. 3405-3410, (November/December 1998).	
	22	Chin C. Hsia, et al., "Customized Off-Axis Illumination Aperture Filtering for Sub 0.18 um KrF Lithography", <u>SPIE Optical Microlithography XI</u> , Vol. 3679, pp. 39-46, (1999).	
	23	P. Zandbergen, et al., "Optical Extension at the 193nm Wavelength", <u>SPIE Optical Microlithography XI</u> , Vol. 3679, pp. 29-38, (1999).	
	24	Z. Yang, et al., "Corrections of Aberrations Using HOE's in UV and Visible Imaging Systems", <u>SPIE International Lens Design Conference</u> , Vol. 1354, pp. 323-327, (1990).	
HN	25	B. W. Smith, <u>Microlithography: Science and Technology</u> , Chapter 3, New York: Marcel Dekker (1998), pp. 216-231.	

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